

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re U.S. Patent Application of )  
FUKUDA et al. )  
Application Number: To Be Assigned )  
Filed: Concurrently Herewith )  
For: MANUFACTURING METHOD FOR ELECTRONIC )  
DEVICE )  
ATTORNEY DOCKET NO. NITT.0250 )

Honorable Assistant Commissioner  
for Patents  
Washington, D.C. 20231

**INFORMATION DISCLOSURE STATEMENT**

Pursuant to 37 C.F.R. §§ 1.56 and 1.97, this Information Disclosure Statement is submitted in the above-identified National Stage U.S. patent application. A listing of documents to be published on the face of any patent granted from this application is submitted herewith on Form PTO-1449. Any other documents or information submitted for consideration by the Examiner are listed in this paper. A copy of each U.S. and foreign patent, or each publication or portion thereof listed or herein identified, is submitted herewith.

**CERTIFICATION**

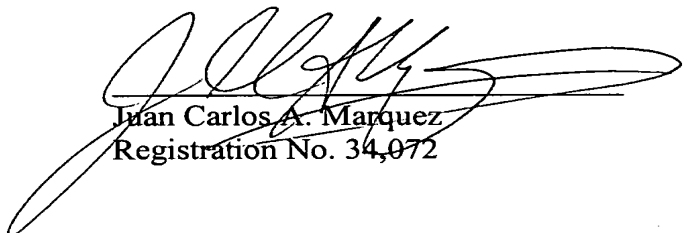
This Information Disclosure Statement is submitted with the initial filing of the application. Accordingly, no fee is due or payable at this time.

The Examiner is requested to acknowledge consideration of the information provided in this paper in accordance with prescribed procedures.

Please charge any additional fees or credit any overpayments in connection with this paper to Deposit Account No. 08-1480.

Respectfully submitted,

\_\_\_\_\_  
Stanley P. Fisher  
Registration Number 24,344

  
Juan Carlos A. Marquez  
Registration No. 34,072

**REED SMITH LLP**  
3110 Fairview Park Drive  
Suite 1400  
Falls Church, Virginia 22042  
(703) 641-4200

**January 27, 2005**

Form PTO 1449  U.S. Department of Commerce Patent and Trademark Office  Information Disclosure Statement by Applicant	ATTY. DOCKET NUMBER NITT.0250	SERIAL NUMBER To be Assigned
	APPLICANT FUKUDA et al.	
	FILING DATE Concurrently Herewith	GROUP

U.S. Patent Documents

Examiner Initial	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE

Foreign Patent Documents

Examiner Initial	DOCUMENT NUMBER	FILING DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION	
						YES	NO

Other Documents (Including Author, Title, Date Pertinent Pages, Etc.)

		Yukinori Ochiai et al., "High-Resolution, High-Purity Calix[n]arene Electron Beam Resist", Journal of Photopolymer Science and Technology, Vol. 13, No. 3 (2000), pp. 413-417
		Tetsuya Tada et al., "Improved Sensitivity of Multi-Adduct Derivatives of Fullerene", Journal of Photopolymer Science and Technology, Vol. 14, No. 4 (2001), pp. 543-546
		Tsuyohiko Fujigaya et al., "A New Photoresist Based on Poly(propyleneimine) Dendrimer", Journal of Photopolymer Science and Technology, Vol. 13, No. 2 (2000), pp. 339-344
EXAMINER		DATE CONSIDERED

PTO1449